

ITEC Seminar

THEME: Multi-Level Modeling of Cultural Effects on Employee Commitment:

Survey Data on Japanese and U. S. Factories in the 1980's

DATE: Friday June 10th, 2011

TIME: 4 PM - 5:30 PM

VENUE: Room KMB 213, Kambaikan Bldg., Doshisha University

Guest Speaker:

Professor James R. Lincoln

Visiting Fellow, ITEC, Doshisha University
The Mitsubishi Professor of International
Business and Finance
Walter A. Haas School of Business
University of California, Berkeley



Speaker Profile:

James R. Lincoln is the Mitsubishi Professor of International Business and Finance at the Walter A. Haas School of Business of the University of California, Berkeley. He is the author (with Michael Gerlach) of Japan's Network Economy: Structure, Persistence, and Change (Cambridge University Press, 2004), (with Arne Kalleberg) Culture, Control, and Commitment: A Study of Work Organizations and Work Attitudes in the U. S. and Japan (Cambridge University Press, 1990), and numerous articles on Japanese business and other topics in organization studies. Most recently, he co-edited (with Asli Colpan and Takashi Hikino) the Oxford Handbook of Business Groups (OUP, 2010).

Abstract:

Using survey data collected in the 1980's from 100 Japanese and U. S. factories and 8,000 of their employees, I present results from an analysis of cultural effects at country and factory levels on employee commitment behaviors; specifically, intent to remain with the firm and willingness to work hard for the firm. Factory–level cultural effects are modeled as two kinds: (1) values and beliefs held by individuals; and effects arising from social pressure or peer influences. The primary finding is that peer influence was more important in Japan than in the U. S. as the mechanism whereby factory culture shaped employee commitment.

The lecture and Q&A will be in English

Organized by:

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